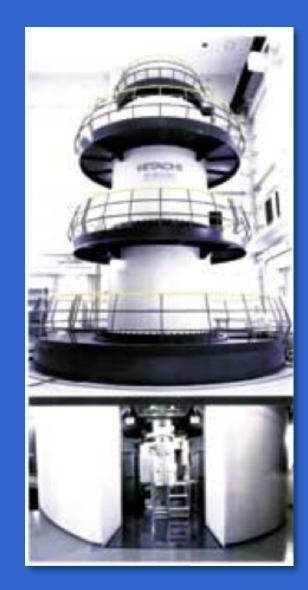
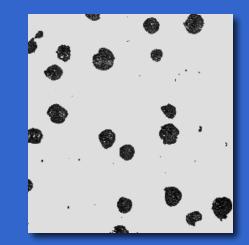
Do it with electrons !



- Structure determines properties
- We have discussed crystal structure (x-ray diffraction) But consider now different level of structure Microstructure (微观结构)- also affects properties



Grey cast iron (灰色生铁) - rather brittle

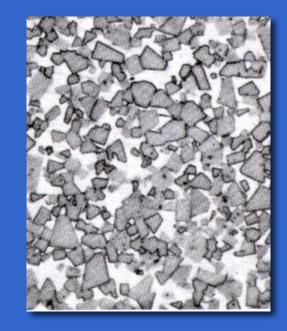


Ductile iron - highly ductile

Structure determines properties We have discussed crystal structure (x-ray diffraction) But consider now different level of structure

Microstructure - also affects properties

Cemented WC (碳化钨) cutting tool



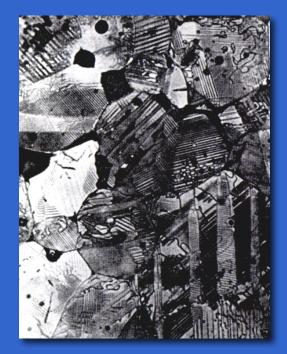
Structure determines properties

We have discussed crystal structure (x-ray diffraction)

But consider now different level of structure

Microstructure - also affects properties

Ferroelectric domains in BaTiO₃

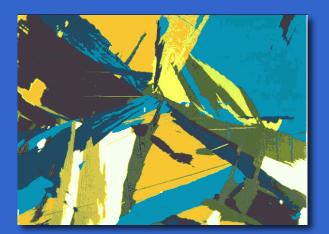


Structure determines properties

We have discussed crystal structure (x-ray diffraction) But consider now different level of structure Microstructure - also can be 'art (美术)'







Electron microscopy

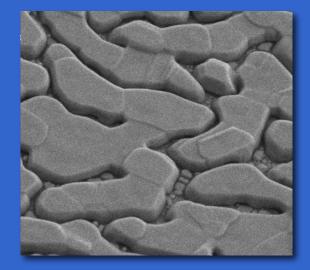
SEM - scanning electron microscopy

tiny electron beam scanned across surface of specimen

backscattered (背散射) or secondary electrons (二次电子) detected

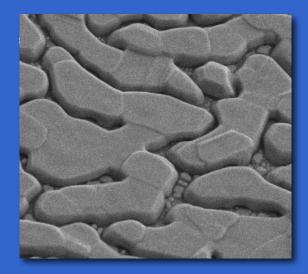
signal output to synchronized display





Electron microscopy SEM - scanning electron microscopy Magnification range 15x to 200,000x Resolution of 50 Å Excellent depth of focus Relatively easy sample prep





Electron gun

Don't make x-rays - use electrons directly

Wavelength:

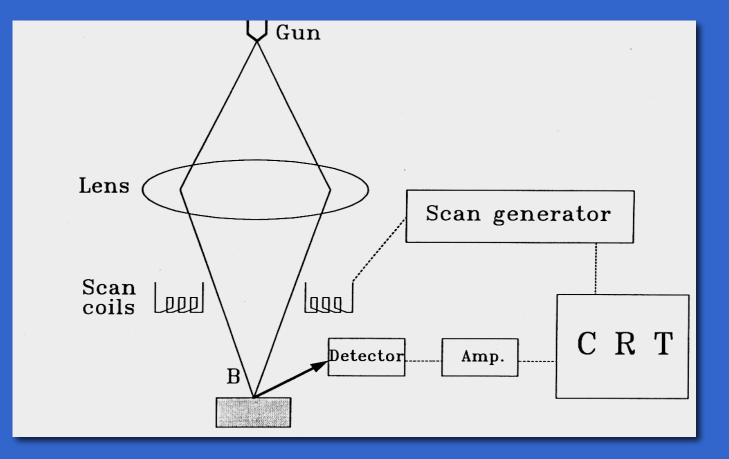
NOT $\lambda = hc/E$ (massless photons)

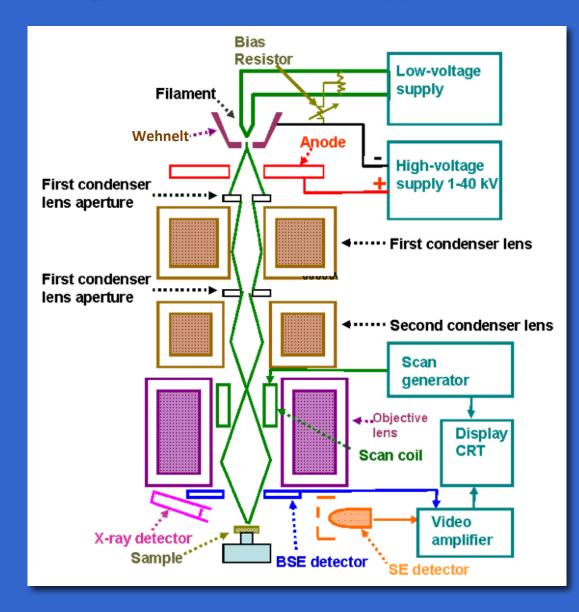
λ = h/(2m_{electron}qV_o)^{1/2} (non-relativistic)

 $\lambda = h/(2m_{electron}qV_{o} + q^{2}V_{o}^{2}/c^{2})^{1/2}$ (relativistic (相对论的))

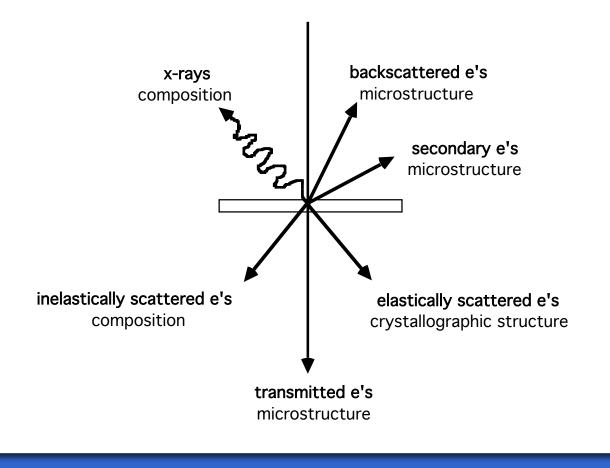
 $\lambda = h / (2m_{electron}qV_{o} + q^{2}V_{o}^{2}/c^{2})^{1/2}$ $\lambda = 1.22639 / (V_{o} + 0.97845 \cdot 10^{-6}V_{o}^{2})^{1/2}$ $\lambda(nm) \& V_{o}(volts)$

10 kV \longrightarrow 0.12 Å 100 kV \longrightarrow 0.037 Å





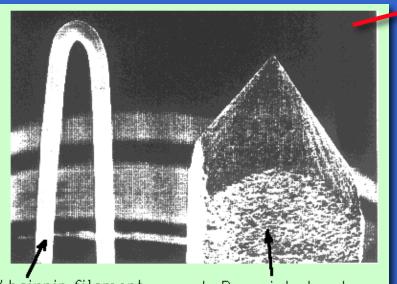




Electron gun

VANN , Bias / Emission Wehnelt grid HT/kV Anode to condenser lenses

Filament current



W hairpin filament 125 micron diam.

LaB₆ pointed rod

Electron emitter

 $\lambda = h/(2m_{electron}qV_o + q^2Vo^2/c^2))^{1/2}$

Effects of increasing voltage in electron gun:

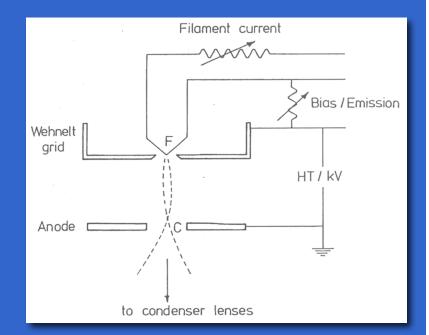
Resolution increased (λ decreased)

Penetration increases

Specimen charging increases (insulators)

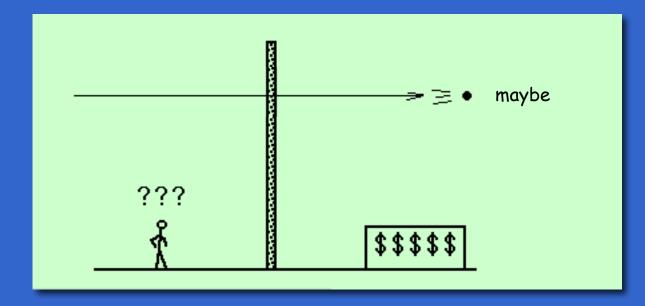
Specimen damage increases

Image contrast decreases



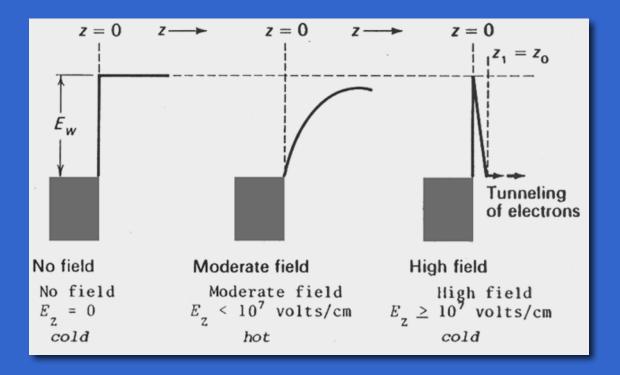
Field emission electron source:

High electric field at very sharp tip causes electrons to "tunnel"



Field emission electron source:

High electric field at very sharp tip causes electrons to "tunnel"



Field emission electron source:

High electric field at very sharp tip causes electrons to "tunnel"

cool tip ——> smaller ΔE in beam improved coherence

many electrons from small tip ——> finer probe size, higher current densities (100X >)

problems - high vacuum, more \$\$\$, fussy

Lenses

electrons focused by Lorentz force from electromagnetic field **F** = q**v** × **B** effectively same as optical lenses

Lenses are ring-shaped

coils generate magnetic field electrons pass thru hollow center

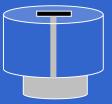
lens focal length is continuously variable

apertures control, limit beam

Specimen

Conducting little or no preparation attach to mounting stub for insertion into instrument may need to provide conductive path with Ag paint

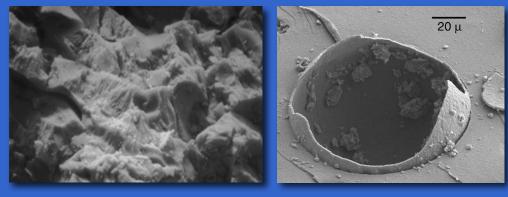


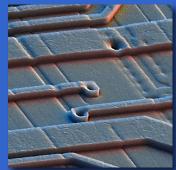


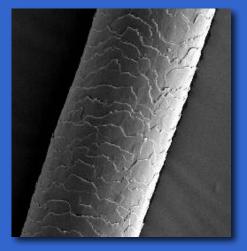
Non-conducting usually coat with conductive very thin layer (Au, C, Cr)

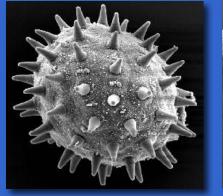
Specimen

Can examine fracture surfaces electronic devices fibers coatings particles etc.











Specimen

Can be tilted, translated

Specimen size limited by size of sample chamber



Specimen

What comes from specimen?

Backscattered electrons

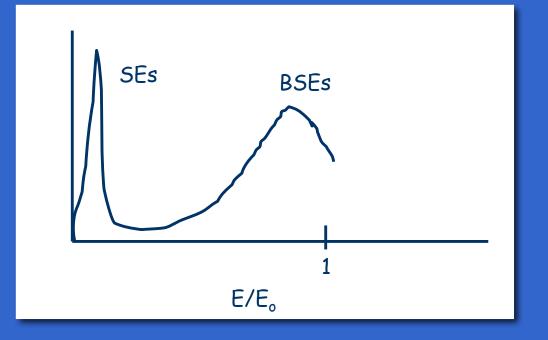
Secondary electrons Fluorescent X-rays

composition - EDS

high energy compositional contrast Brightness of regions in image increases as atomic number increases (less penetration gives more backscattered electrons)

> low energy topographic contrast

Electron energy distribution



Backscattered electron detector - solid state detector

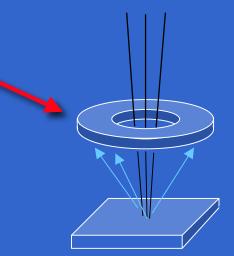
electron energy up to 30-50 keV

annular around incident beam

repel secondary electrons with — biased mesh

images are more sensitive to chemical composition (electron yield depends on atomic number)

line of sight necessary

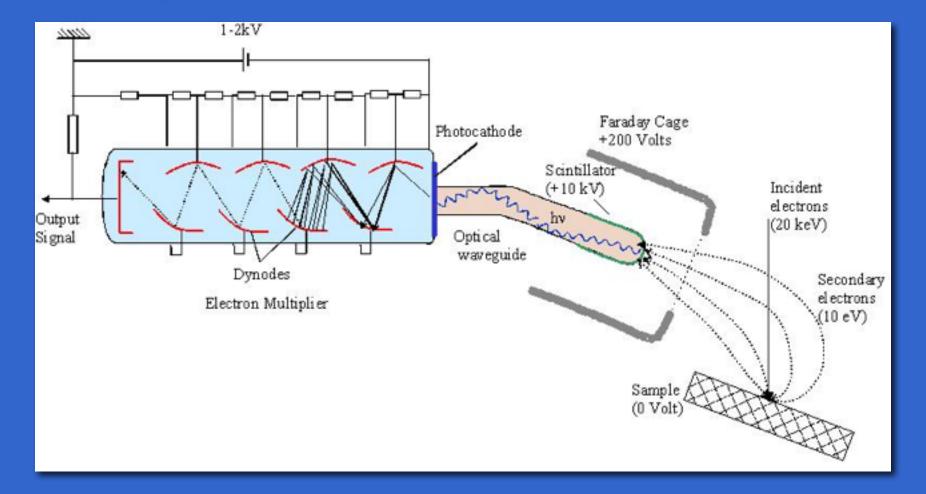


Secondary electron detector - scintillation detector

+ bias mesh needed in front of detector to attract low energy electrons

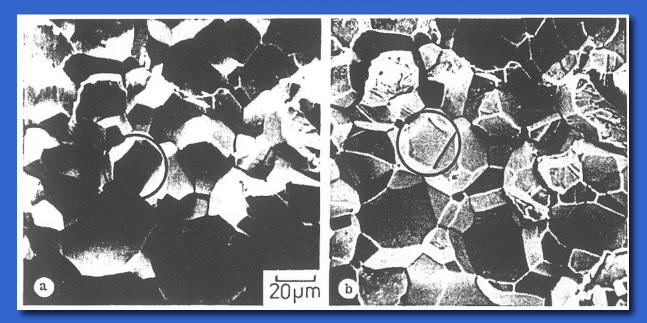
line of sight unnecessary

Secondary electron detector - scintillation detector



Choose correct detector- topography example

Fracture surface in iron

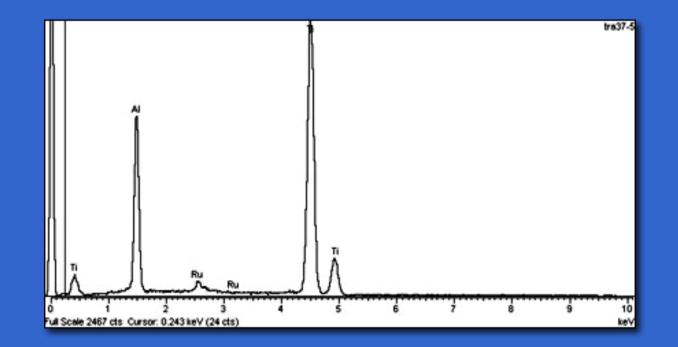


backscattered electrons secondary electrons

Composition - what elements present at a particular spot in specimen?

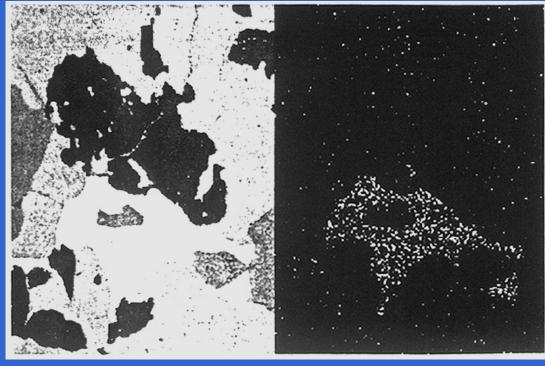
Use solid state detector

Do energy scan for fluorescent X-rays



Composition mapping - x-ray fluorescence

Use solid state detector set for X-ray energy for a particular element in specimen



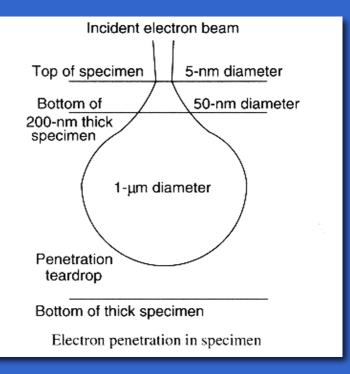
image



Interaction volume

Backscattered electrons come from whole volume (high energy)

Secondary electrons come from neck only (low energy)

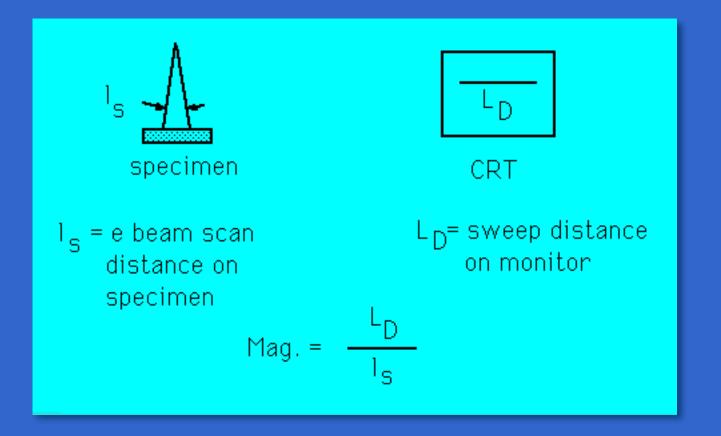


Contrast

Comes from any kind of interaction with electron beam topography composition elements phases grain (crystal) orientation

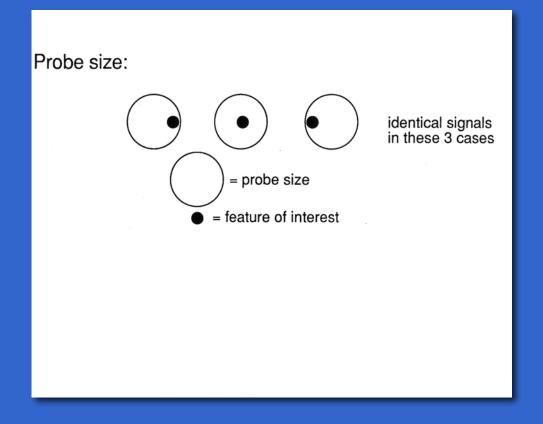
charging affects contrast

Magnification



Resolution

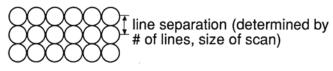
Determined by probe size



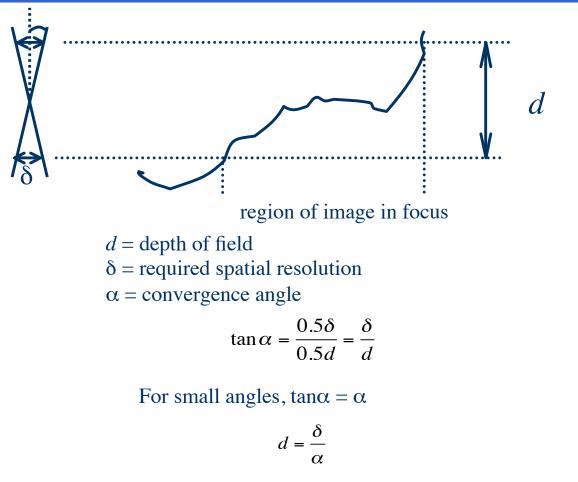
Resolution

Determined by probe size

Optimum probe size:



Depth of field



Can control depth of field (*d*) with convergence angle (α)

Depth of field

